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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of:

J. KONNO et al

Serial Number: 07/743,383

Filed: August 21, 1991

For: METHOD FOR PRODUCING SEMICONDUCTOR INTEGRATED CIRCUITS  
AND APPARATUS USED IN SUCH METHOD

GROUP 110

Group Art Unit: 1104

Examiner: G. Goudreau

RESPONSE UNDER 37 CFR 1.115

Honorable Commissioner  
of Patents and Trademarks  
Washington, D.C. 20231

December 27, 1993

Dear Sir:

In response to the Official Action dated August 25, 1993, the period for response to which having been extended for one (1) month to expire December 25, 1993 by reason of a petition and a fee therefore filed herewith, kindly amend the above identified application as follows:

IN THE CLAIMS:

Please amend the claims as follows:

1. (Twice Amended) A method for producing semiconductor integrated circuits, comprising the steps of:

a first step of selectively etching a metallic film formed on a surface of a substrate and exposed through a mask made of a resist which selectively covers said metallic film, by [using] effectively contacting said metal exposed through said mask with a